

A practical introduction to scanning electron microscopy

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mag 🗖	HFW	20 μm
4 041 x	73.8 µm	Nova NanoSEM: IChF PAN



Practical information

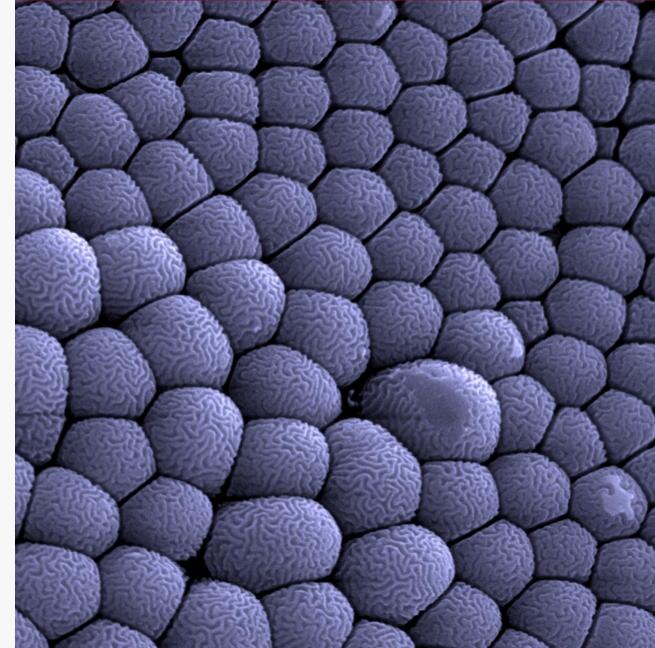
4 hours lectures4 hour practicals (groups of 3)

Exam: Measure "mystery sample" Analyse images (size, composition) Hand in report

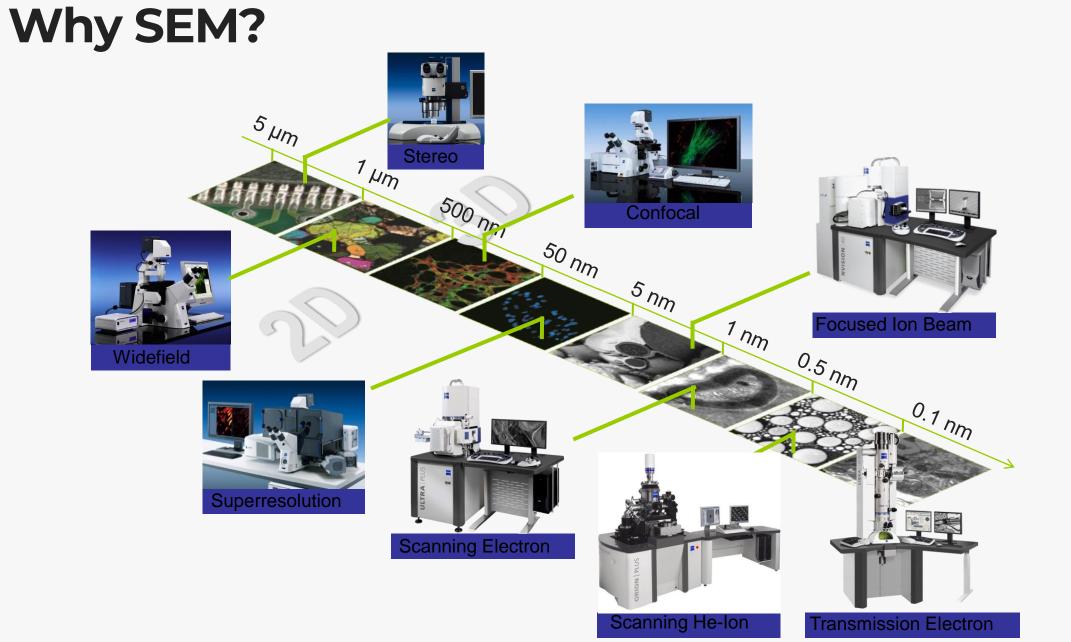
Info on www.charge-transfer.pl/sem-course

Content

Basic principles Electron-matter interaction Settings and limitations Different detection modes Our system Sample preparation EDX / WDX

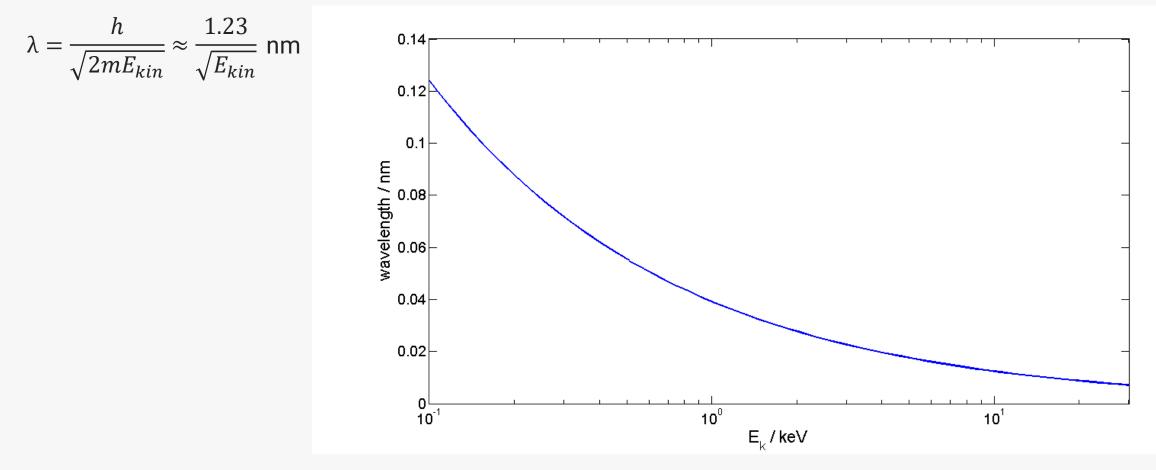




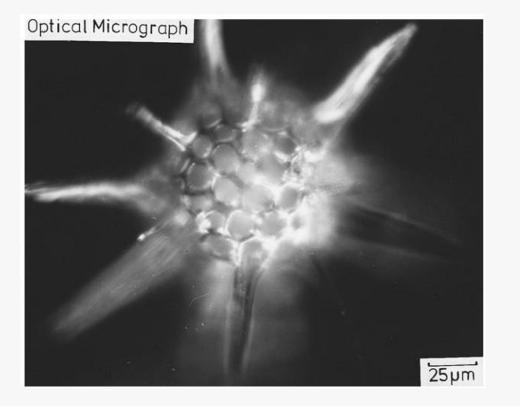


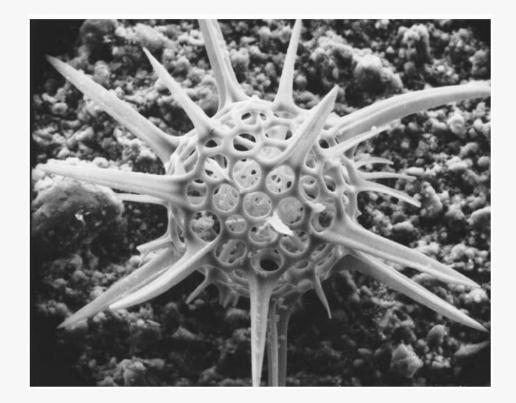


de Broglie wave-length







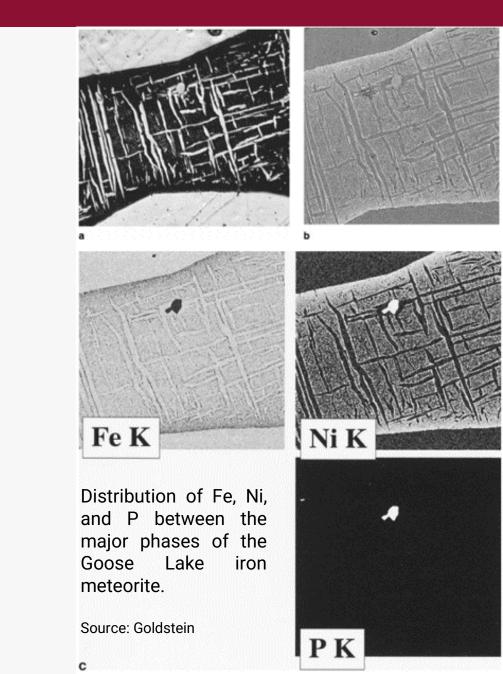


Optical and SEM micrograph of the radiolarian Trochodiscus longispinus



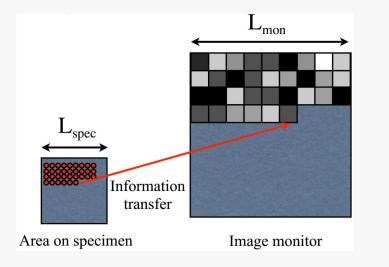
Why SEM?

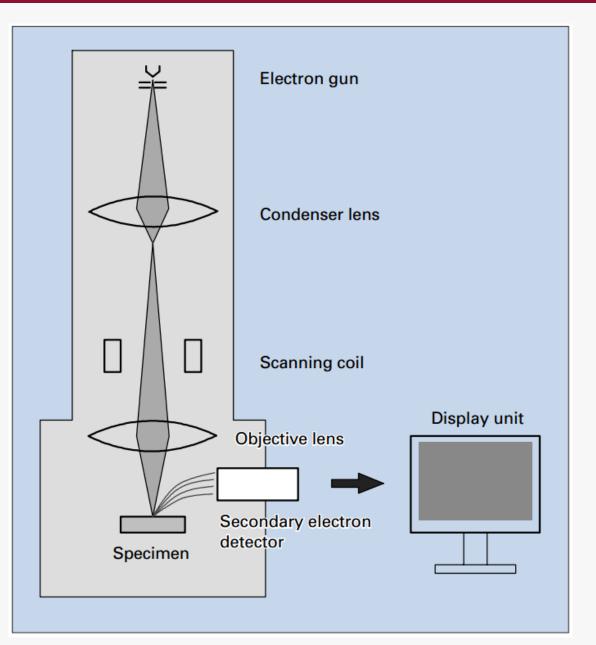
- Versatile
- . Topography
- Elemental information
- Crystallinity
- . Fast
- Non-destructive (mostly)
- Easy (mostly)





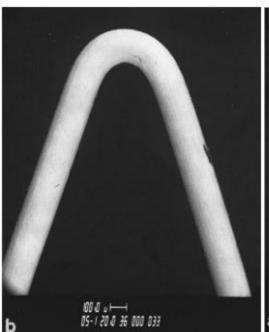
Working principle

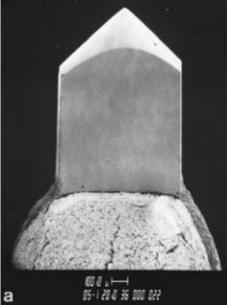


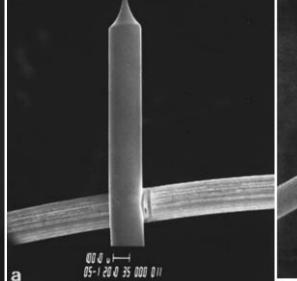


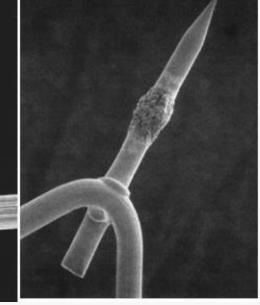


ectron gun	TE gun		EE aup	
Jeeu on gan	Tungsten	LaB ₆	FE gun	SE gun
Electron-source size	15 ~ 20 µm	10 µm	5 ~ 10nm	15 ~ 20nm
Brightness (Acm ⁻² rad ⁻²)	10 ⁵	10 ⁶	10 ⁸	10 ⁸
Energy spread (eV)	3~4	2~3	0.3	0.7 ~ 1
Lifetime	50 h	500 h	Several years	1 to 2 years
Cathode temperature (K)	2800	1900	300	1800
Current fluctuation (per hour)	<1%	<2%	>10%	<1%









Tungsten wire thermionic emitter

8

Lanthanum hexaboride thermionic emitter

Tungsten singly-crystal cold field emission tip

Tungsten/ZrO₂ Schottky field emission tip

Source: Goldstein

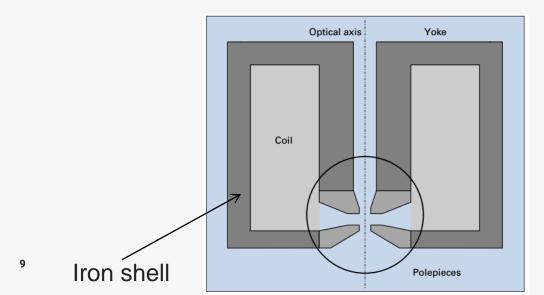


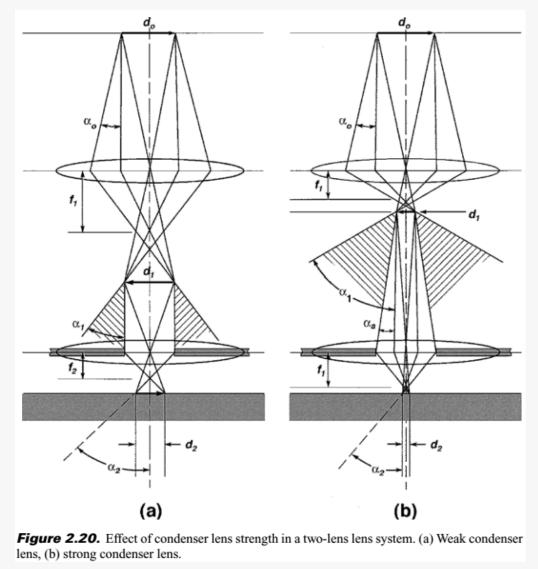
In SEM magnetic lenses are used. Cylindrically symmetric "Soft magnetic" shell Field leaks out at narrow gap. Only the pole pieces need to be very accurately fabricated

Focal length of the lens can be changed

 $f \approx V_0 / (NI)^2$

Beam is twisted through the lens

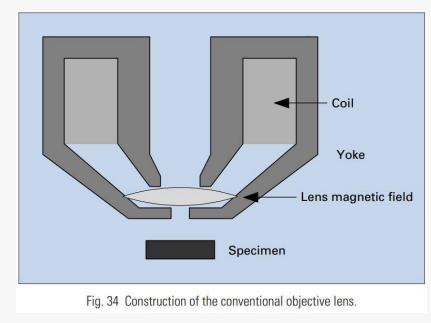




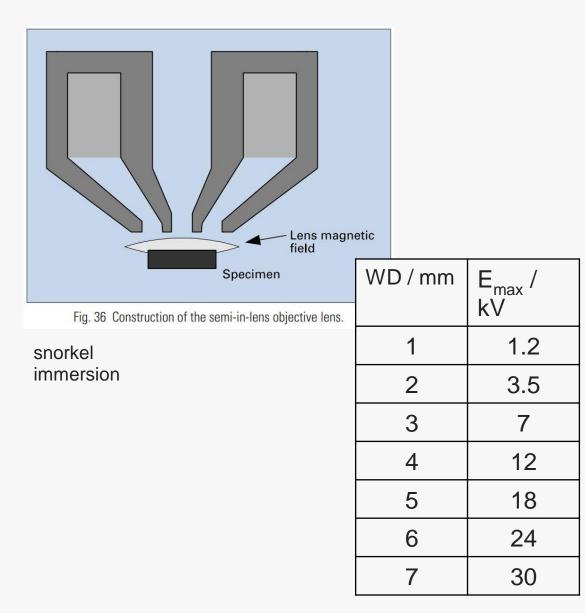
Weak lens ('large spot')

 \rightarrow Higher current \rightarrow Lower resolution





Snorkel / immersion: •Higher resolution •Lower max field of view (min ca 1500x) •Only in-lens detector •Restriction on magnetic materials •Limit on usable voltages

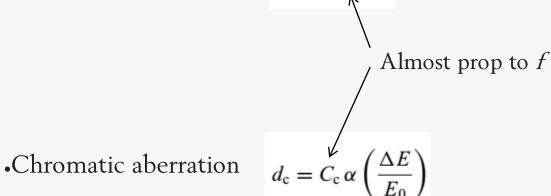


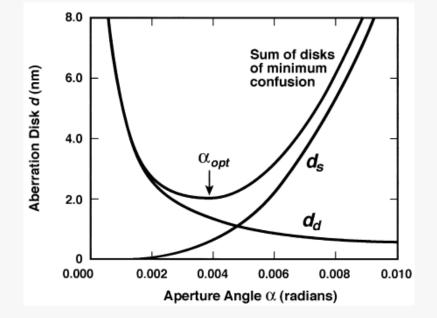


Resolution is given by probe diameter (size of electron beam)

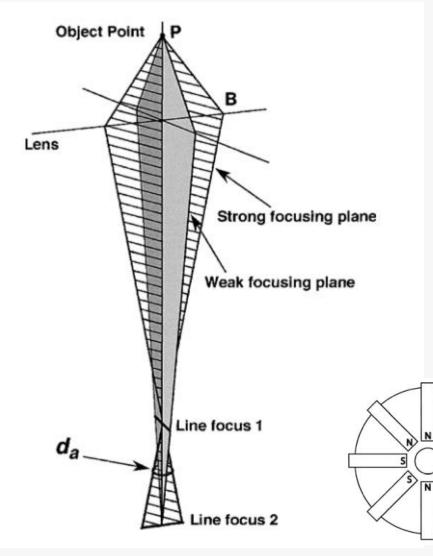
•Gaussian beam diameter (no aberration) $d_{\rm G} = \sqrt{}$

•Diffraction in aperture •Spherical aberration $d_s = \frac{1}{2}C_s\alpha^3$,

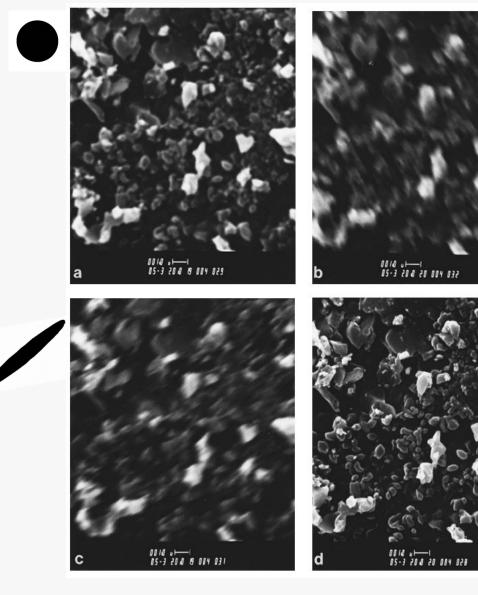






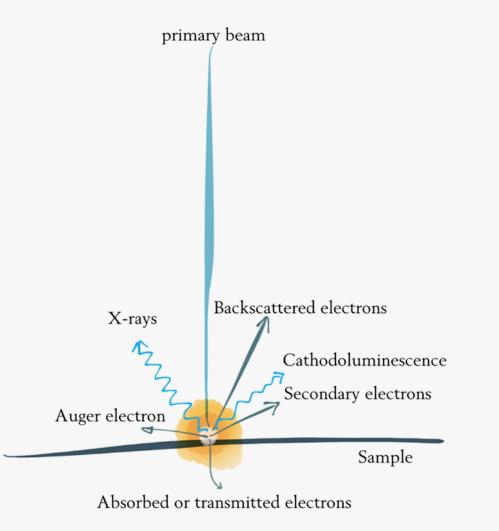


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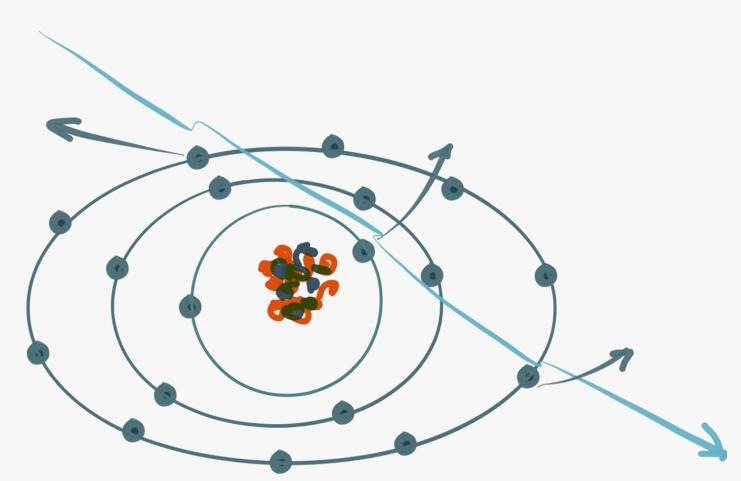
Electron matter interaction





Secondary electrons

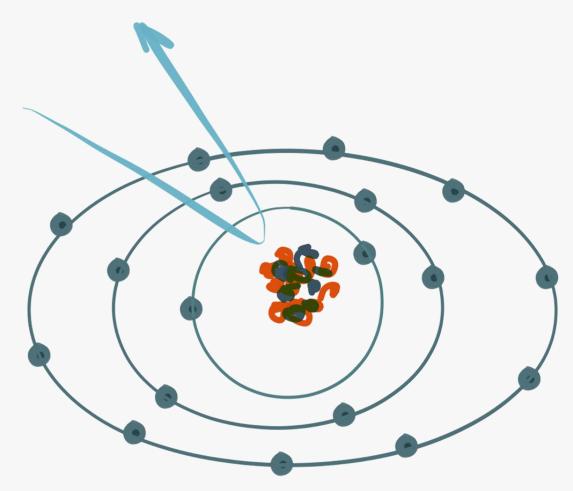
- Non-elastic collision
- Electrons come from inside the atoms in the sample.
- Low energy
- Information about surface topography





Backscattered electrons

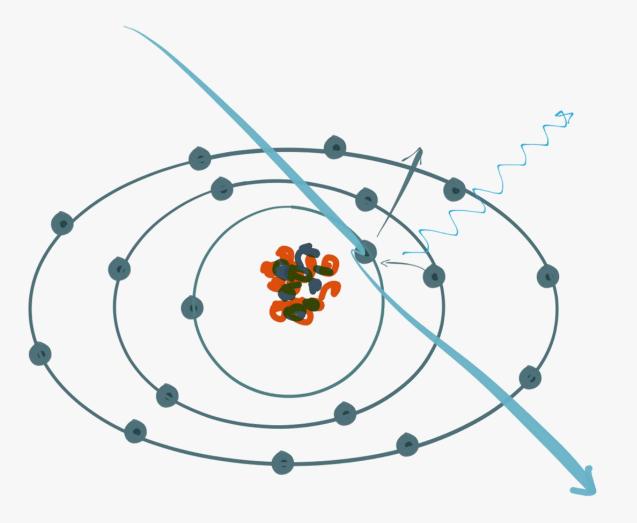
- 。 (Almost) elastic collision
- Electrons come from the primary beam.
- High energy
- Probes deeper into the sample
- Some information about elemental composition





X-ray emission

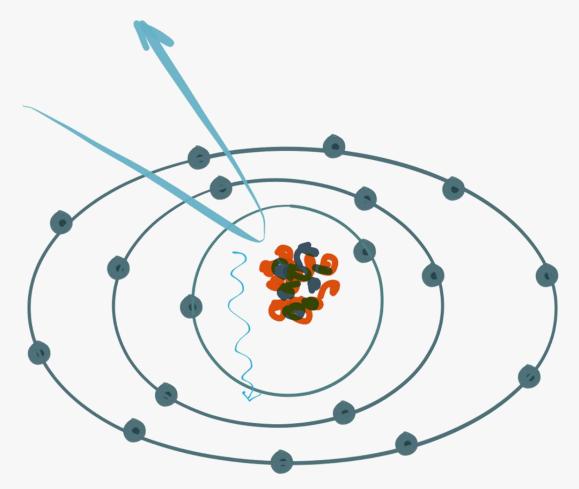
- X-ray emission sent out when an electron emitted from an inner shell and another outer electron fills the hole
- Specific elemental information.
- Basis of EDX.





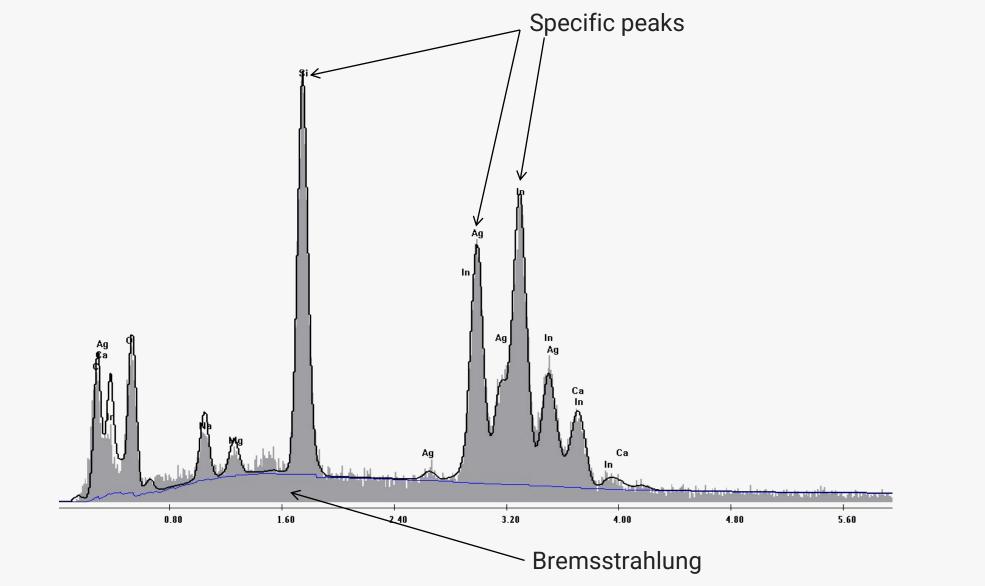
X-ray emission (Bremsstrahlung)

- X-ray emission sent out when an electron is accelerated.
- No elemental information.
- Forms background in EDX



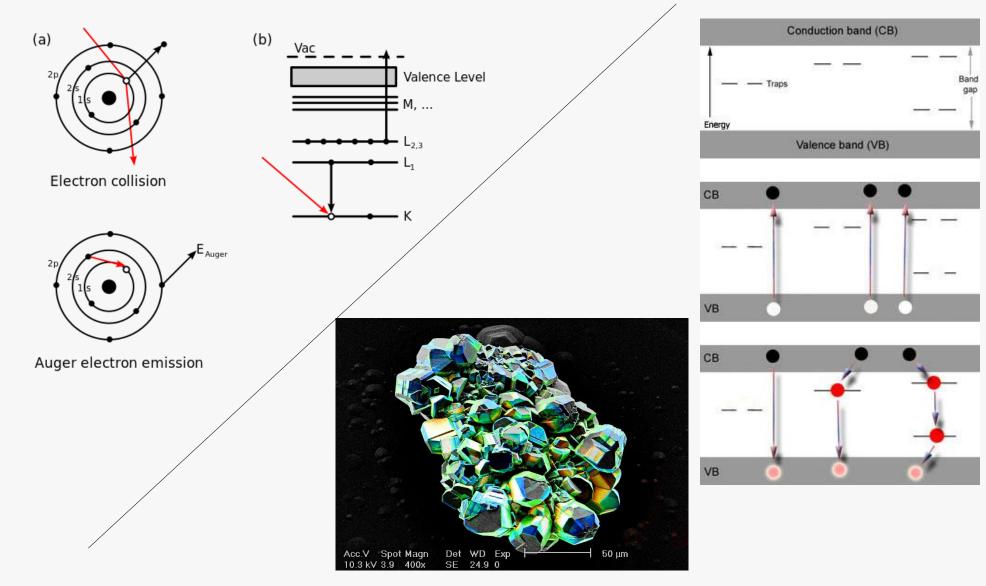


X-ray emission



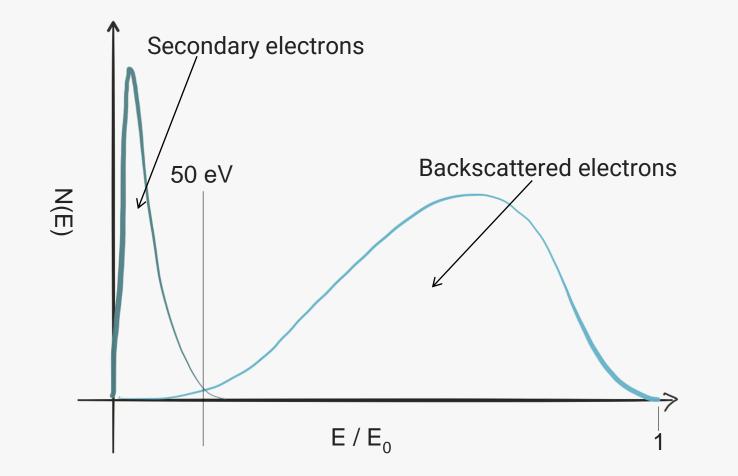


Auger electrons / Cathode luminescence





Types of electrons?

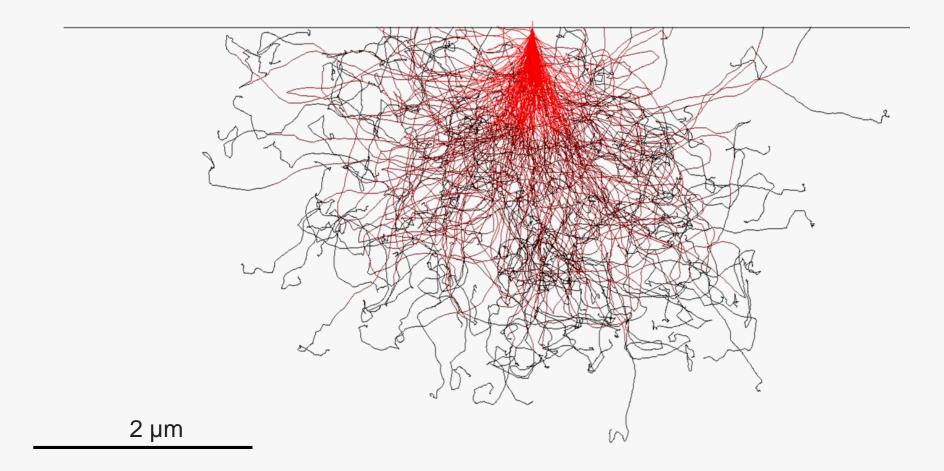




Interaction volume

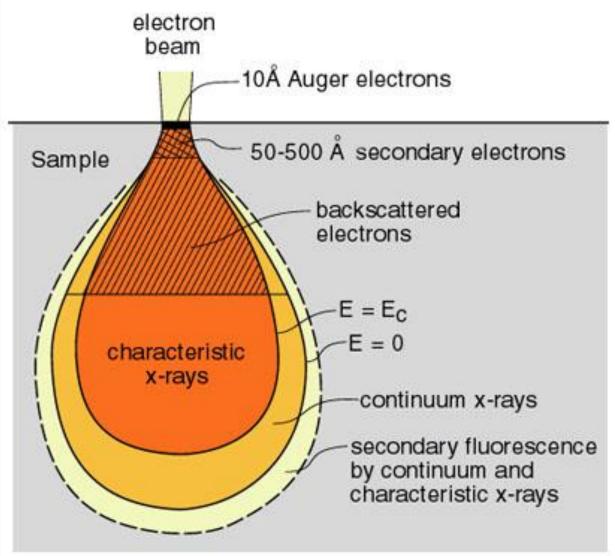
A Practical Introduction to SEM

20 kV beam in Si



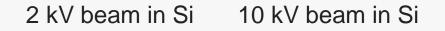


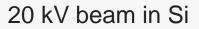
Interaction volume

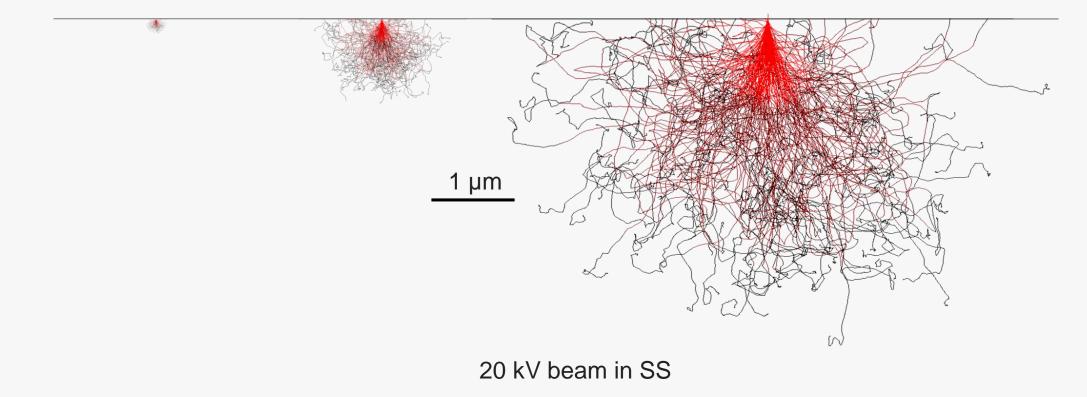




Interaction volume





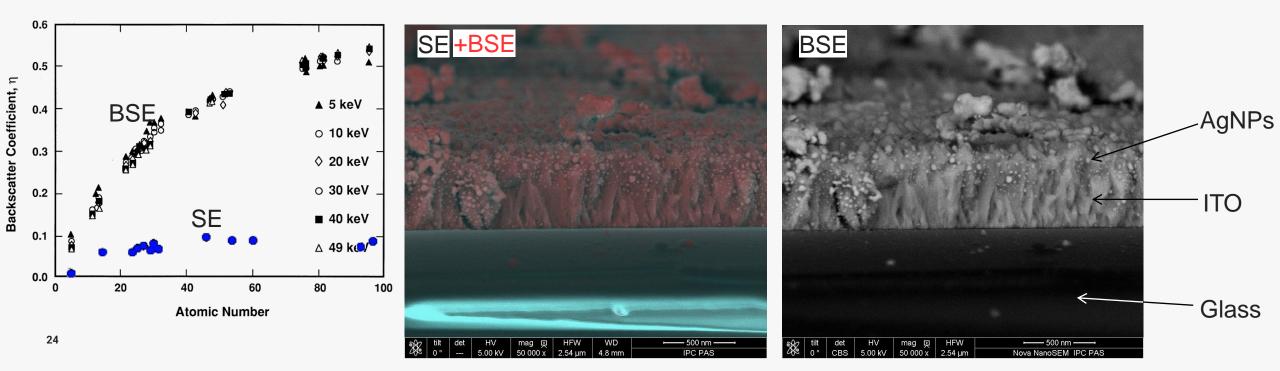




Backscatter efficiency

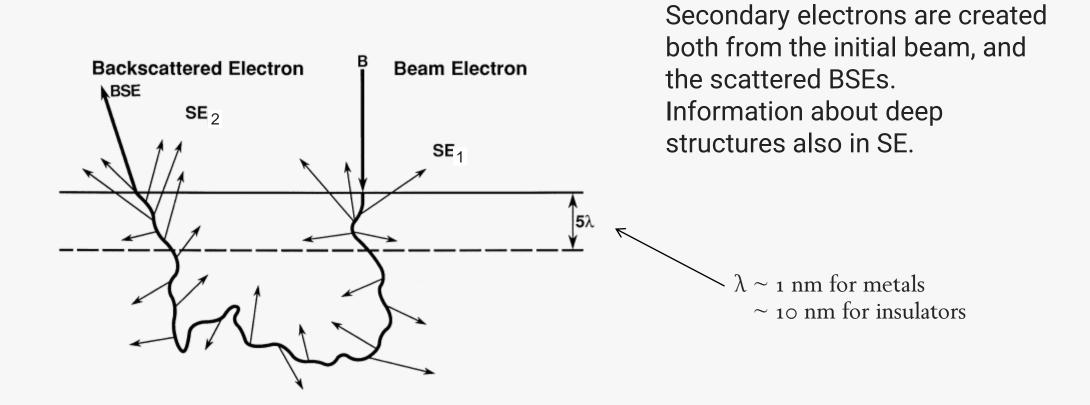
Backscatter efficiency is element dependent, but relatively insensitive to energy.

$$C = \frac{\eta_1 - \eta_2}{\eta_2} \ \eta = \sum_i C_i \eta_i,$$



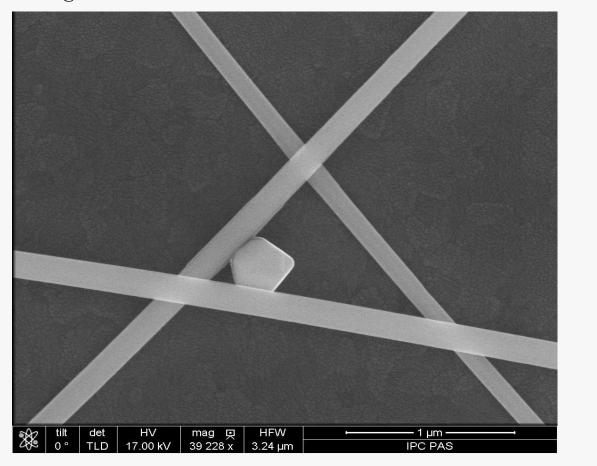


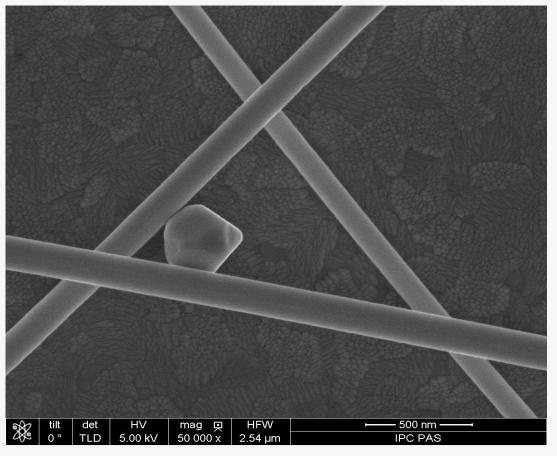
Secondary electrons



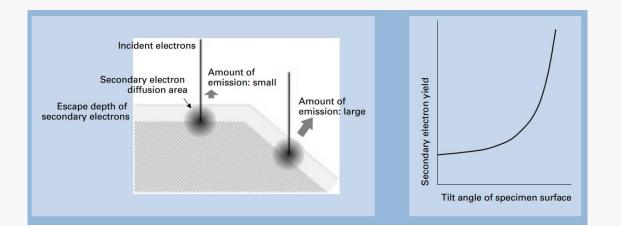


SE images of nanowires with different acceleration voltages.









SE yield is strongly angledependent.→ bright sides of structures

Edge effect also gives oversaturated edges.

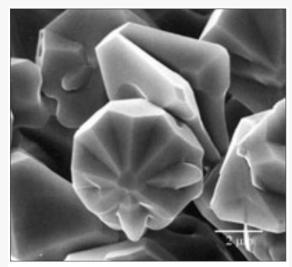
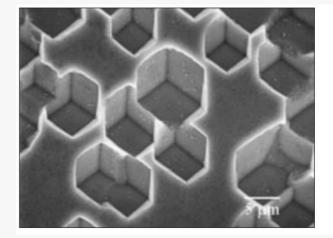
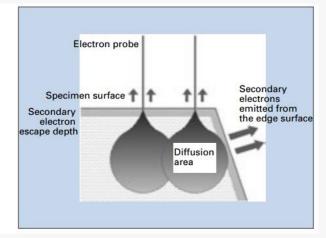


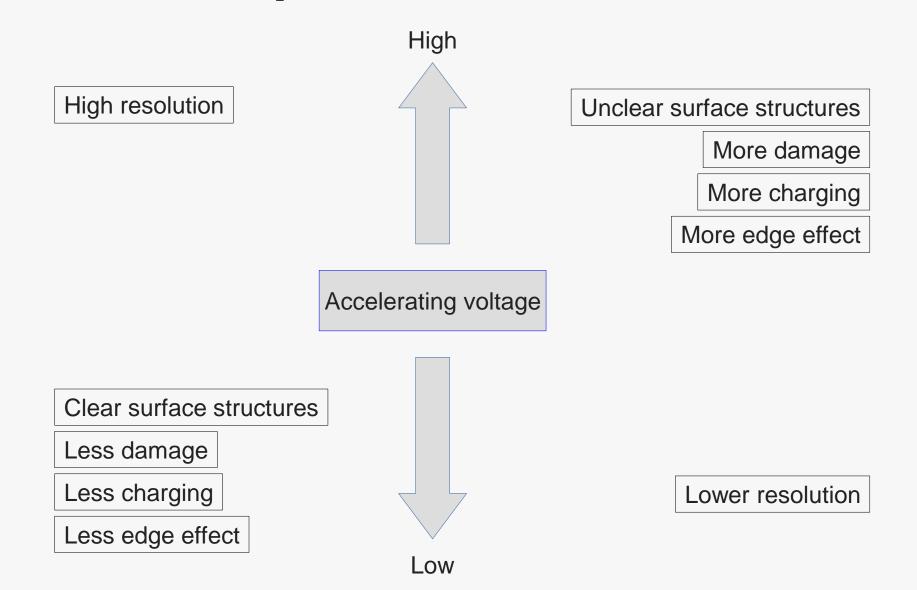
Fig. 15 Secondary electron image of tungsten oxide crystal.





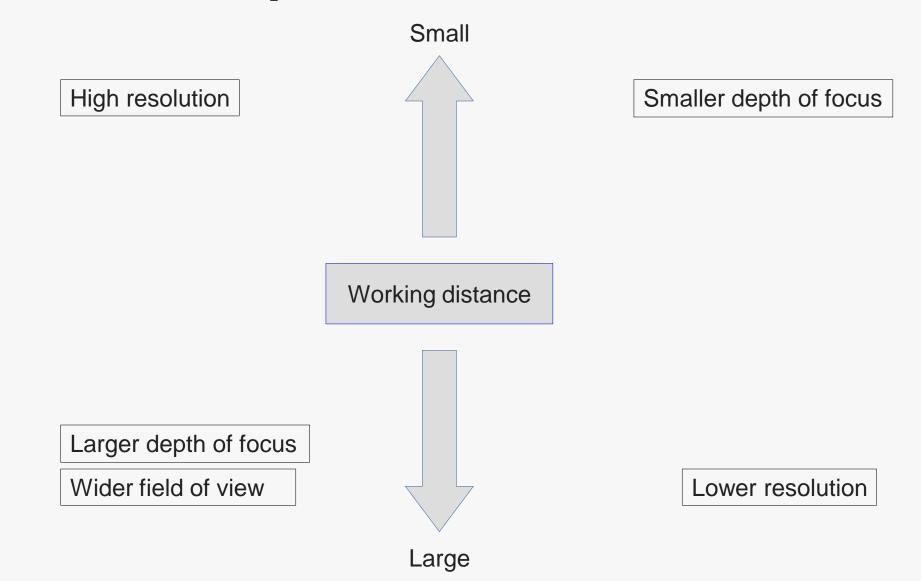


A game of compromises



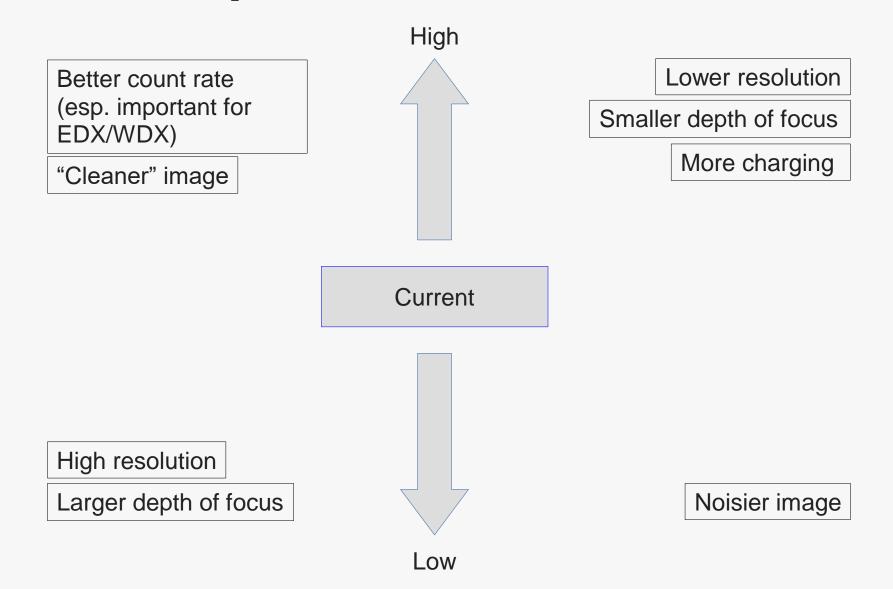


A game of compromises





A game of compromises





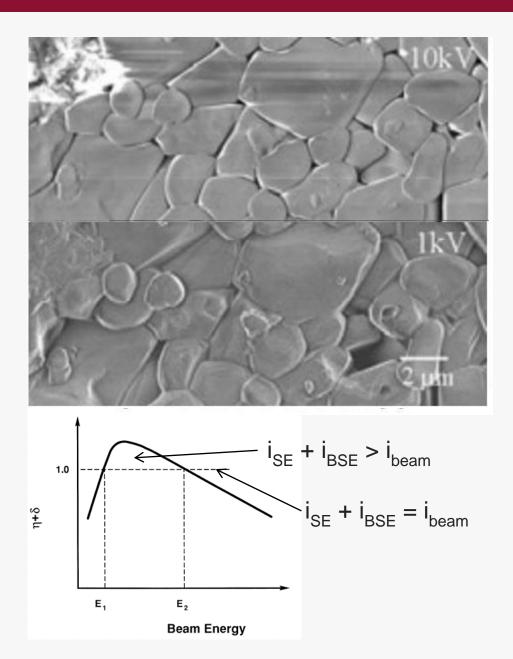
Charging

Charging occurs when the sample, or part of the sample, is not sufficiently conductive.

- → Anomalous contrast Too bright, too dark. Often changing over time
- \rightarrow Distortion

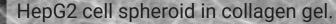
Material	$E_2(\text{keV})$	Reference
Kapton	0.4	Joy (unpublished)
Electron resist	0.55-0.70	Joy(1987)
Nylon	1.18	Joy (unpublished)
5% PB7/nylon	1.40	Krause et al. (1987)
Acetal	1.65	Vaz (1986)
Polyvinyl chloride	1.65	Vaz (1986)
Teflon	1.82	Vaz and Krause (1986)
Glass passivation	2.0	Joy (1987)
GaAs	2.6	Joy (1987)
Quartz	3.0	Joy (1987)
Alumina	4.2	Joy (unpublished)

Table 3.6. Upper Crossover Energy for Various Materials (Normal Beam Incidence)



How to avoid charging?

- Lower voltage Lower current
- Faster scanning & image integration Line interlacing
- Tilting the sample
- BSE instead of SE
- Low vacuum mode
- Coating the sample





Tack ör uppmärksamheten

∃ękuję za uwagę

k you for your attention

Contact: Martin Jönsson-Niedziółka email: martinj@ichf.edu.pl Twitter: @DrMartinJN